ma-P 1275 and ma-P 1275 HV – Positive Tone Photoresists

**Characteristics**
- Specifically designed for electroplating of structures in microsystems technology
- High stability in acid and alkaline plating baths
- Well suitable also for the use as an etch mask exhibiting high dry and wet etch resistance
- Good thermal stability of the resist patterns attainable
- Aqueous alkaline development
- Easy removal
- Side wall angle up to 87° with mask aligner broadband exposure

**Applications**
- Mould for electroplating – e.g. for micro coils, micro springs, micro optical components
- Etch mask for metal and semiconductor substrates – e.g. micro lenses from reflowed patterns
- Mask for ion implantation

**Process flow**

**Film thicknesses**

<table>
<thead>
<tr>
<th>Film thickness</th>
<th>μm</th>
<th>7.5</th>
<th>11</th>
<th>20</th>
<th>30</th>
<th>40</th>
<th>50</th>
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<tr>
<td>ma-P 1275</td>
<td>rpm s</td>
<td>3000</td>
<td>500</td>
<td>350</td>
<td>250</td>
<td>–</td>
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<tr>
<td>ma-P 1275 HV</td>
<td>rpm s</td>
<td>3000</td>
<td>1100</td>
<td>700</td>
<td>500</td>
<td>400</td>
<td>60</td>
</tr>
</tbody>
</table>

**Spin curves**

**UV/vis spectra**

Pattern transferred into OrmoComp by twofold UV moulding